

FORM PTO - 1449

INFORMATION DISCLOSURE STATEMENT

ATTORNEY DOCKET NO.: ASC-001C1

APPLICANT(S): Hammond et al.

SERIAL NO.: 10/688,003

FILING DATE: October 17, 2003

GROUP: Not yet assigned 28//

			U.S.	PATENT I	OCUMI	ENTS				
EXAM. INIT.		DOCUMENT NUMBER	DATE	NAME			CLASS	SUB CLASS	1	NG DATE IF ROPRIATE
ATT	Al	4,908,681	03/13/1990	Nishida et a	d.					7
1	A2	5,534,713	07/09/1996	Ismail et al.						
	A3	5,557,231	09/17/1996	Yamaguchi	et al.					
	A4	5,672,995	09/30/1997	Hirase et al.						
	A5	5,692,002	11/25/1997	Mizutani			,			
	A6	5,877,056	03/02/1999	Wu et al.			ĺ			
	A7	6,040,208	03/21/2000	Honeycutt e	t al.					7
	A8	6,284,615	09/04/2001	Pinto et al.						7
	A9	6,310,367	10/30/2001	Yagishita et	al.					T^{-}
	A10	6,313,016	11/06/2001	Kibbel et al			_			1
	All	6,448,840	09/10/2002	Kao et al.						
STITH	A12	6,680,496	01/20/2004	Hammond e	et al.		257	192	07/0	8/2002
			FOREIG	GN PATEN	T DOCU	MENTS				
EXAM. INIT.		DOCUMENT NUMBER	DATE	COUNTRY CODE	CLASS	SUB CLASS	FILING DATE	ABSTR. ONLY	ACT	ENGLISH LANG (Y/N)
EXAM. INIT.	ОТН	ER DOCUMEN		Author, Title	e, Date, Re	levant Pag	es, Place o			
RUM	CI	Burd et al., "A 35, No. 11 (No.	vember 2000), p	p. 1571-1580.		•				
J	C2	Gonzalez et al., State Circuits,	"Supply and Ti /ol. 32, No. 8 (/	hreshold Volta August 1997),	ge Scaling pp. 1210-1	for Low Po 216.	ower CMO	S," IEEE J	ournal	of Solid-
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24 Von Kaenel et al., "Automatic Adjustment of Threshold & Supply Voltages for Minimum Power Consumption in CMOS Digital Circuits," IEEE Symposium on Low Power Electronics (1994), pps. 78-79.										
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SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

ATTORNEY DOCKET NO.: ASC-001C1

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			U.S.	PATENT I	DOCUMENTS	S		
EXAM. INIT.		DOCUMENT NUMBER	DATE	NAME		CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
RTATA	A13	2002/0008289	01/24/2002	Murota et a	ıl.			
MIKA	A14	2002/0030203	03/14/2002	Fitzgerald				
	A15	2002/0104993	08/08/2002	Fitzgerald (at al.			/]
4	A16	2002/0123167	-09/05/2002	Fitzgerald			-	
_	- A17	2002/0123183	09/05/2002	Fitzgerald				
	-A18	2002/0125497	09/12/2002	Fitzgerald				
	A19	2003/0013323	01/16/2003	Hammend	et al.			
	- A20	2003/0052406	03/20/2003	Lochtefeld	et al.			/
	A21	3003/0077867	04/24/2003	Fitzgerald	Í			/
	- A22	-2003/0102498	-06/05/2003	Braithwaite	et al.			
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SEKKA	A24	4,212,019	07/08/1980	Wataze el d	al.			
1	A25	4,771,013	09/13/1988	Curran				·
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SIKM	A34	5,898,342	04/27/1999	Bell		17		
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			U.S.	PATENT	DOCUMI	ENTS	_					
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MATh	A35	6,052,380	04/18/2000	Bell								
1	A36	6,111,267	08/29/2000	Fischer et	al.		357	19				
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	A38	6,140,687	10/31/2000	Shimomu	ra et al.					7		
	A39	6,160,274	12/12/2000	Folkes						7		
	A40	6,271,726	08/07/2001	Fransis et	al.							
	A41	6,555,839 -	04/29/2003	Fitzgerald	l		257	19				
	A42	6,583,015	06/24/2003	Fitzgerald	l et al.							
	A43	6,593,191	07/15/2003	Fitzgerald			-					
1	A44	6,593,641	07/15/2003	Fitzgerald								
HTKI	A45	6,646,322	11/11/2003	Fitzgerald	l 				07/1	6/2001		
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-	ВІ	01/93338-A-	12/06/2001 44 4,55,839	wo				N		γ		
	- D2	02H3262 A2 cornes ponds to	02/14/2002	WO -				N		Y		
	B3	02/071488 A1		∕wo —				N		Ÿ		
	B4	02/071491-A1	09/13/3002	wo -				N		Υ] /	
•	B5	02/071493 A3	09/13/3003	WO				N		Υ	\	pub aft 7/0
	-B6	02/071495-A1	09/12/2002	WO				N		<u>v</u>] (7/0
	97	02/103760 A2	12/27/2002	wô				N -		¥	1)	•
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		OTHER ART, JOUR	NAL ARTICLES, ETC.				
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2 MM	C5	Abidi et al., "Power-Conscious Design of \ (October 2000), pp. 1528-1545.	Vireless Circuits and Systems," [EEE-2000, Vol. 88, Issue 10				
1	C6		Scaling on CMOS RF Devices and Circuits," <u>IEEE 2000 Custom</u> . 361-364.				
	C7		'0.25µm T-Gate Strained Si/Si0.55Ge0.45 N-MODFET's," IEEE,				
ANTA	C8	Ansley et al., "Based Profile Optimization	for Minimum Noise Figure in Advanced UHV/CVD SiGe HBTs," and Techniques, Vol. 46, No. 5 (May 1998), pp. 653-660.				
	CO_	Armstrong et al., "Technology for SiGe He	terostructure-Based CMOS Device," PhD Thesis, Massachusetts				
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1	CII	Borovitskaya et al., "On Theory of I/F Noi (July 2001), pp. 1067-1069.	se in Semiconductors," Solid-State Electronics, Vol. 45, Issue 7				
	C12	Brouk et al., "Dimensional Effects in CMC (January 2002), pp. 19-28.	S Photodiodes," Solid-State Electronics, Vol. 46, Issue I				
	C13	Chatterjee et al., "SUM-100NM Gate Leng Gate Process," IEEE, (1997), pp.1-4.	th Metal Gate NMOS Transistors Fabricated by a Replacement				
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	C16	Chew et al., "Driving CMOS into the Wire 2001 Custom Integrated Circuits Conference	less Communications Arena with Technology Scaling," IEEE				
	C17	Choi et al., "A Low Noise On-Chip Match Wireless LAN Applications," IEEE – GaA	ed MMIC LNA of 0.76DB Noise Figure at 5 GHz for High Speed				
	C18	Choi et al., "Low Noise PHEMT and its M	MIC LNA Implementation for C-Band Applications," IEEE neter Wave Technology Proceedings, (2000), pp. 56-59.				
 	C19		New Contender for Si-Based RF and Microwave Circuit				
		Applications," IEEE Transactions on Micr 572-589.	owave Theory and Techniques, Vol. 46, Issue 5 (May 1998), pp.				
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SCHOK	C21	Enciso-Aguilar et al., "De-Embedded Ultra - Electron Device Letters, Vol. 37, Issue 2	a-Low Noise 0.1 µM Gate Length Ge/Si0.4Ge0.6 P-Modfet," IEEE				
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STRY	C22	Enciso-Aguilar et al., "0.3DB Minimum No	sise Figure at 25 GHz of 0.13 µM Si/Si0.58Ge0.42 N-				
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	C25	Gilbert et al. "Analog at Milepost 2000: A	Personal Perspective," <u>IEEE-2001</u> , Vol. 89, Issue 3 (March				
	000	2001), pp. 289-304.					
	C26	Gray et al., "Analysis and Design of Analog Edition (1984), pp. 604-688.	Integrated Circuits," John Wiley & Sons Publishing Co., Second				
	C27	Harame et al., "Optimization of SiGe HBT Applications," IEEE-IEDM 93 Conference,	Technology for High Speed Analog and Mixed Signal				
	C28	Harame et al., "Si/SiGe Epitaxial-Base Tran	sistors Part II: Process Integration and Analog Applications,"				
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	C30	Huang et al., "The Impact of Scaling Down	to Deep Submicron on CMOS RF Circuits," IEEE Journal of				
 	<u> </u>	Solid State Circuits, Vol. 33, Issue 7 (July	icmos Technology II: Design, Technology and Performance,"				
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	C32	Kar et al., "Estimation of Hole Mobility in	Strained Sil-xGex Buried Channel Heterostructure PMOSFET,"				
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	C34	Kim et al., "Novel RF Isolation Structures	Using Porous Si," University of California, Los Angeles, CA,				
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	C37	Konig et al., "SiGe HBTs and HFETs," So 1595-1602.	lid-State Electronics, Vol. 38, Issue 9 (September 1995), pp.				
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